
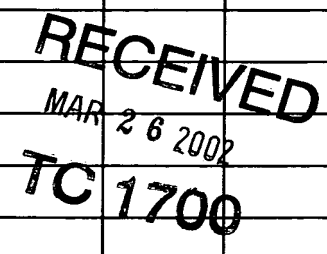


Form PTO 1449 U.S. DEPARTMENT OF (Modified) COMMERCE PATENT AND TRADEMARK OFFICE		DOCKET NO. 5988-036-27		SERIAL NO. 09/987,916	
LIST OF REFERENCES CITED BY APPLICANT (Use Several Sheets if Necessary)		APPLICANT AKI SUZUKI, ET AL.		GROUP ART UNIT 1752	
		FILING DATE NOVEMBER 16, 2001			



U.S. PATENT DOCUMENTS							
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE	
ACW	AA	5,238,774	08/24/93	Hosaka, et al.			
	AB	5,215,857	06/01/93	Hosaka, et al.			
	AC	5,405,720	04/11/95	Hosaka, et al.			
	AD	5,494,784	02/27/96	Hosaka, et al.			
	AE	5,925,492	07/20/99	Hosaka, et al.			
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	AJ	6,337,171 B1	01/08/02	Kobayashi, et al.			
AK	RE37,179 E	05/15/01	Yamachika, et al.				



FOREIGN PATENT DOCUMENTS						
DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES NO			
ACW	AL	60-191372	09/28/85	Japan	Abstract	
	AM	61-212131	09/20/86	Japan	Abstract	
	AN	03-232652	10/16/91	Japan	Abstract	
	AO	2000-284482	10/13/00	Japan	Abstract	

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)		
AP	Jiro NAKAMURA, et al., "Resist Surface Roughness Calculated using Theoretical Percolation Model", Journal of Photopolymer Science and Technology, Vol. 11, No. 4, pp. 571-576, (1998).	
AQ	Peter ZANDBERGEN, et al., "Characterization and optimization of positive tone DUV resists on TiN substrates", SPIE Vol. 3049, pp. 314-323.	
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AT	Hideo NAMATSU, et al., "Three-dimensional siloxane resist for the formation of nanopatterns with minimum linewidth fluctuations", J. Vac. Sci. Technol. B, Vol. 16, No. 1, pp. 69-76 (1998).	

EXAMINER <i>John C. Walk</i>	DATE CONSIDERED <i>March 26, 2003</i>
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*EXAMINER: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.